--- Supplementary Information ---

Atomic layer deposition of ternary ruthenates by combining metalorganic precursors with RuO_4 as the co-reactant

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Supplementary Figures

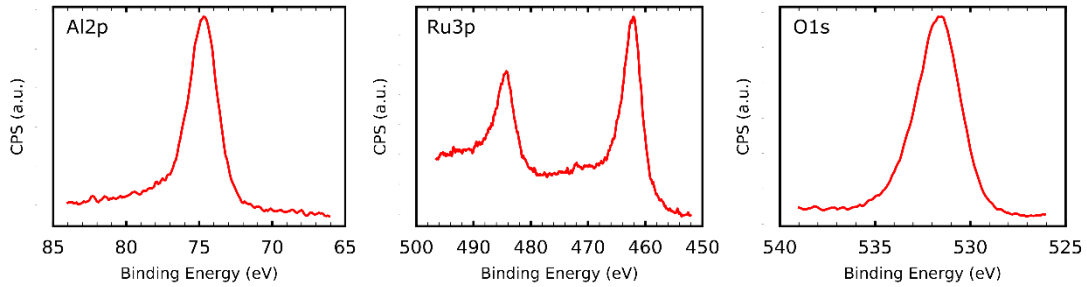

Fig. S1. XPS spectra acquired after 4000 s of depth profiling using a 1 kV Ar^+ ion beam on a thin film deposited by the TMA/RuO_4 process.

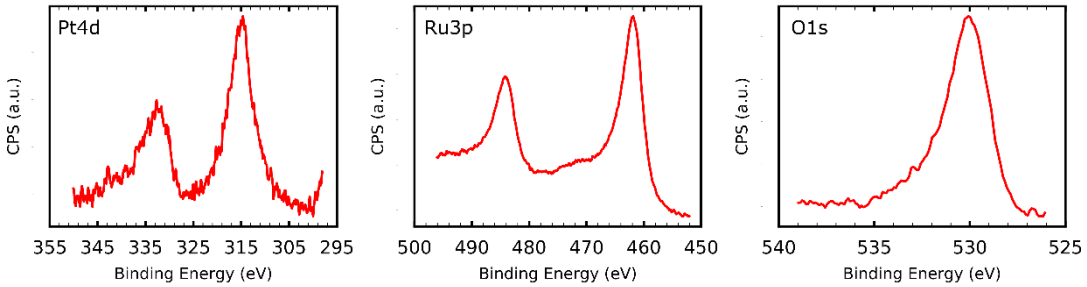

Fig. S2. XPS spectra acquired after 125 s of depth profiling using a 3 kV Ar^+ ion beam on a thin film deposited by the MeCpPtMe_3/RuO_4 process.